

# Thermal emittance and response time from NEA photocathodes

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# **Talk outline**

- Theoretical maximum beam brightness
- Introduction to NEA cathodes
- Inelastic scattering mechanisms
- Diffusion model
- Thermal emittance & response time
- Temporal laser pulse shaping



- Assuming a pan-cake bunch at the cathode [ $\sigma_t << (\sigma_x m/eE_{cath})^{1/2}$ ] max charge density that can be extracted dq/dA =  $\epsilon_0 E_{cath}$
- For Gaussian distribution of transverse momenta characterized by thermal energy kT, <px<sup>2</sup>> = mkT
- Normalized average beam brightness ( $\Delta x$ ,  $\Delta p_x$  ... ellipse half-axes)  $B_{n,avg} \equiv I_{avg}(mc)^2/(\pi \Delta x \Delta p_x \pi \Delta y \Delta p_y)$
- Max brightness per bunch:

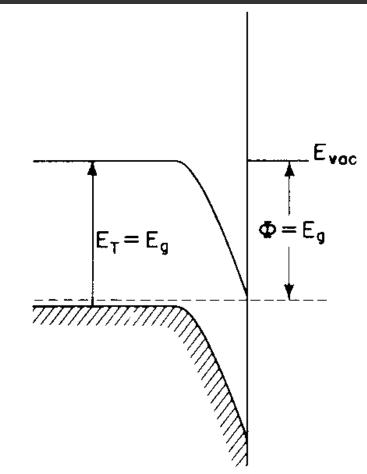
$$\frac{B_{n,avg}}{f} = \frac{\mathcal{E}_0 mc^2}{8} \frac{E_{cath}}{kT}$$



# Cornell University Negative Electron Affinity

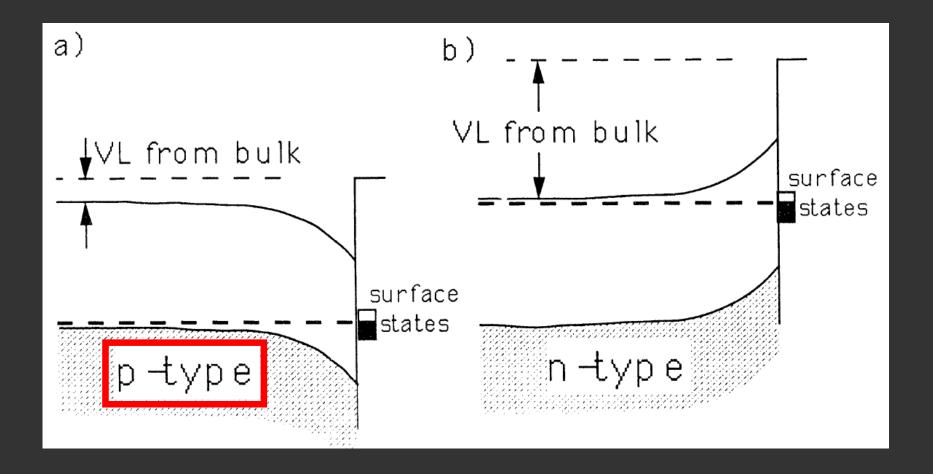
- Defined as vacuum level E<sub>vac</sub> relative to the bottom of conduction band
- Negative affinity means the vacuum level lies below the conduction band minimum ⇒ very high QE
- Surface condition induces

   a space charge, which may
   bend the bands either up or
   down





# **NEA:** doping

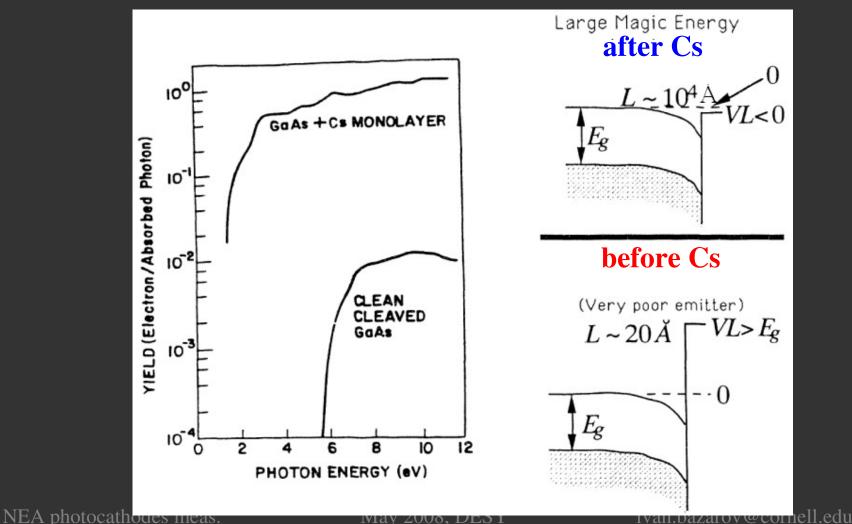


NEA photocathodes meas.



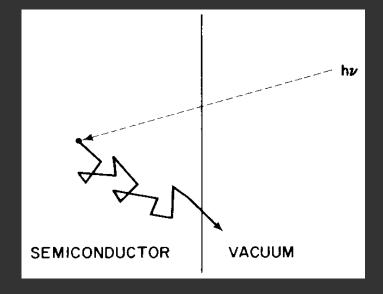
# **NEA: Cs monolayer**

If thickness of a low work function material << mean free path  $\Rightarrow e^{-}$  can traverse the surface material without much loss  $\Rightarrow$  better quantum efficiency / reduced threshold





# Spicer's 3-step model



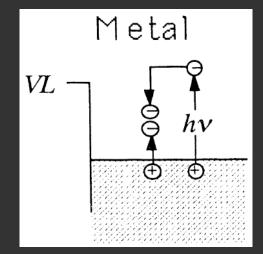
- 1. photon excites electron to a higherenergy state;
- electron-phonon scattering (~0.01– 0.05 eV lost per collision);
   escape with kinetic energy in excess to E<sub>vac</sub>

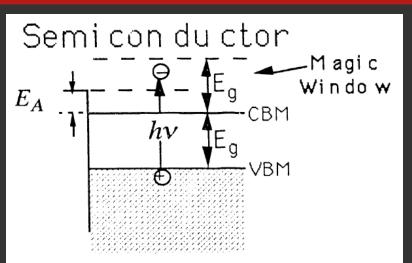
In GaAs the escape depth is long enough that a large fraction of electrons are thermalized to the bottom of the conduction band before they escape.

Response time ~  $(10^{-4} \text{ cm})/(10^7 \text{ cm/s}) = ~10 \text{ ps}$ strong wavelength dependence!



# Inelastic scattering





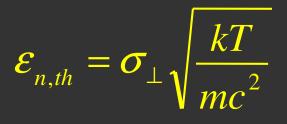
(1) Electron-electron scattering: occurs in metals, large energy loss per collision

- (2) Electron-phonon scattering: slowly depletes excessive energy of excited electron
- (3) "Magic window": in semiconductors, one needs excess KE >  $E_{gap}$  for  $e^{-}/e^{-}$  scattering. Thus, electrons excited with  $E_{vac} < KE < E_{VBM} + 2E_{gap}$  have excellent chances of escape (high QE)



# Cornell University Thermal emittance meas.

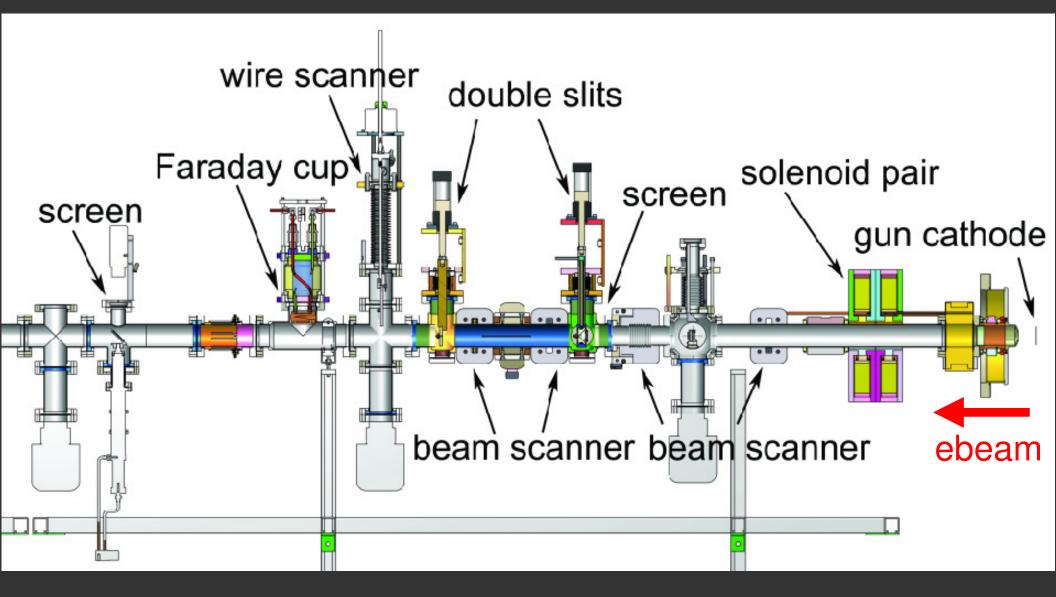
 Thermal emittance was measured as a function of laser wavelength for GaAs and GaAsP(P = 45%)



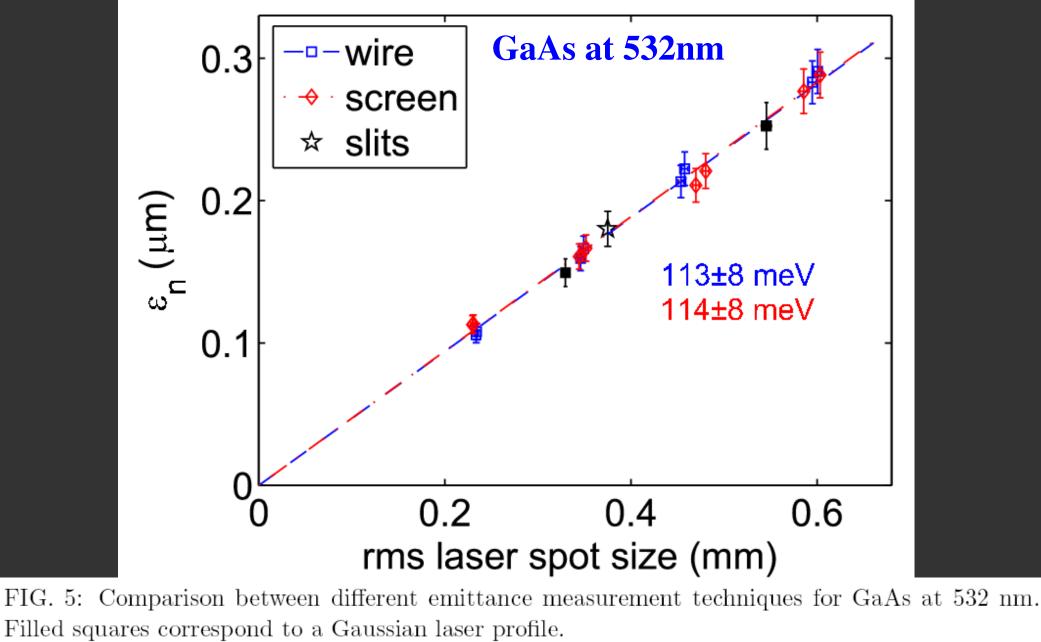
- Emittance was measured by solenoid scan using a wirescanner for different laser spot sizes and profiles
- Essential to take data for various laser spot sizes, cross-check between various methods (e.g. solenoid scan and double-slits, viewscreen & wirescanner)
- See J. App. Phys. 103 (2008) 054901 for details



# Setup (therm. emit.)



# Cornell University Getting methods to agree

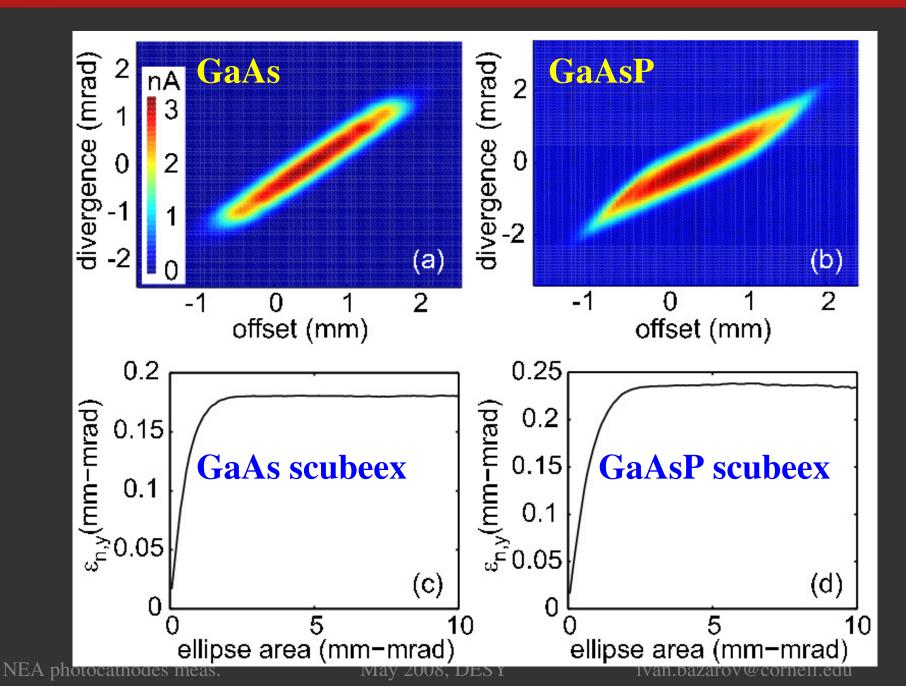


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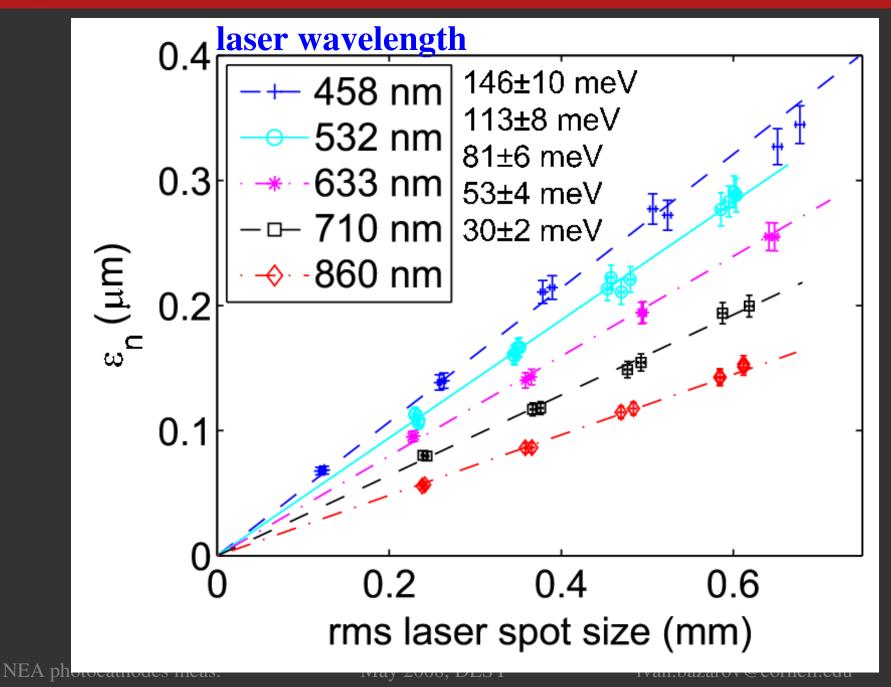


### **Double-slit check**













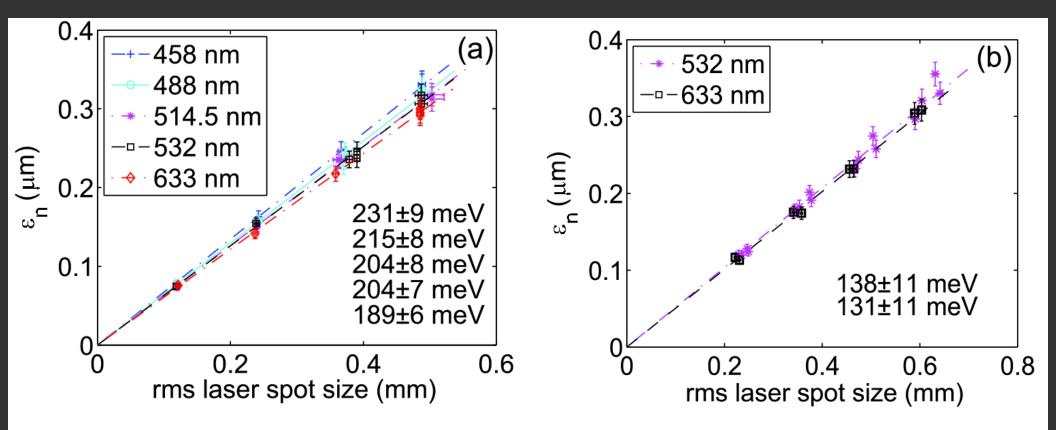
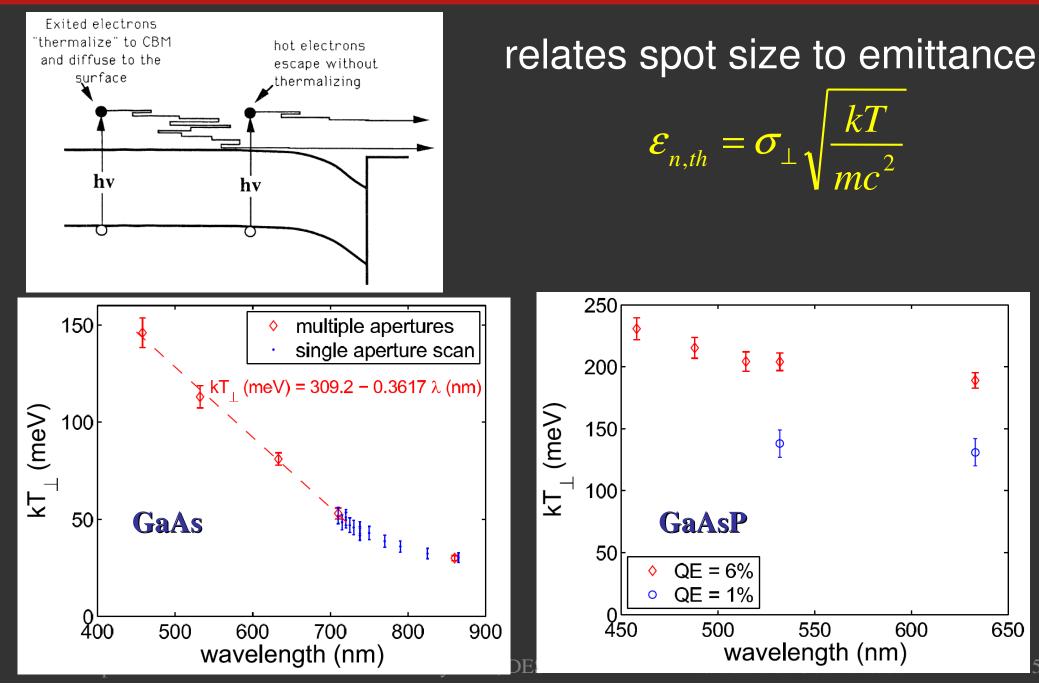


FIG. 7: Thermal emittance of GaAsP as a function of rms laser spot size. (a) QE = 6%. (b) QE = 1%. can see QE effect on thermal emittance for GaAsP!

NEA photocathodes meas



# kT vs. wavelength



650

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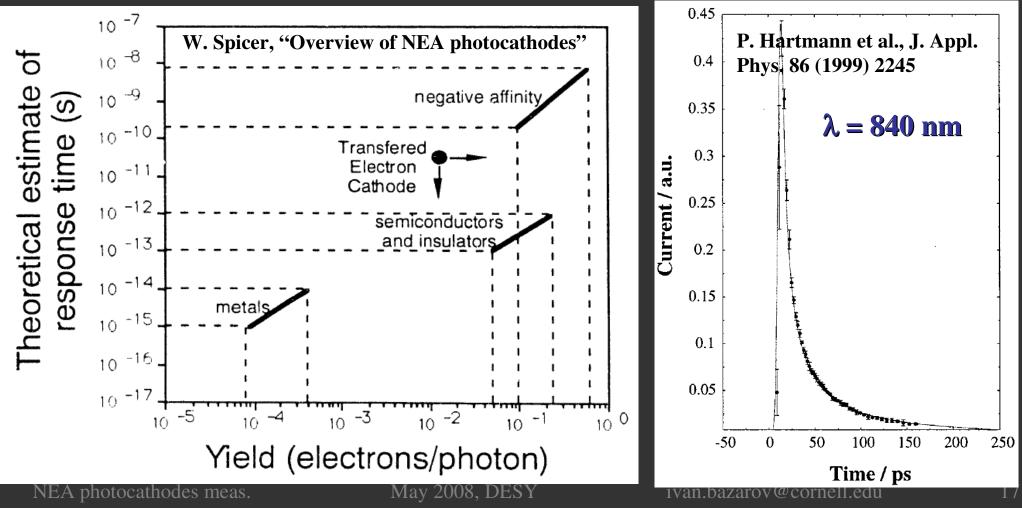
600



- When GaAs excited near the bandgap, electrons come out essentially thermalized (kT ~ 30 meV)
- Shorter wavelength  $\Rightarrow$  smaller thermalized fraction  $\Rightarrow$  larger kT
- GaAsP has larger kT than GaAs despite smaller  $hv_{\text{ph}}\text{-}E_{\text{gap}}$
- GaAsP shows QE dependence for kT, GaAs does not show such dependence within the uncertainty of the measurement

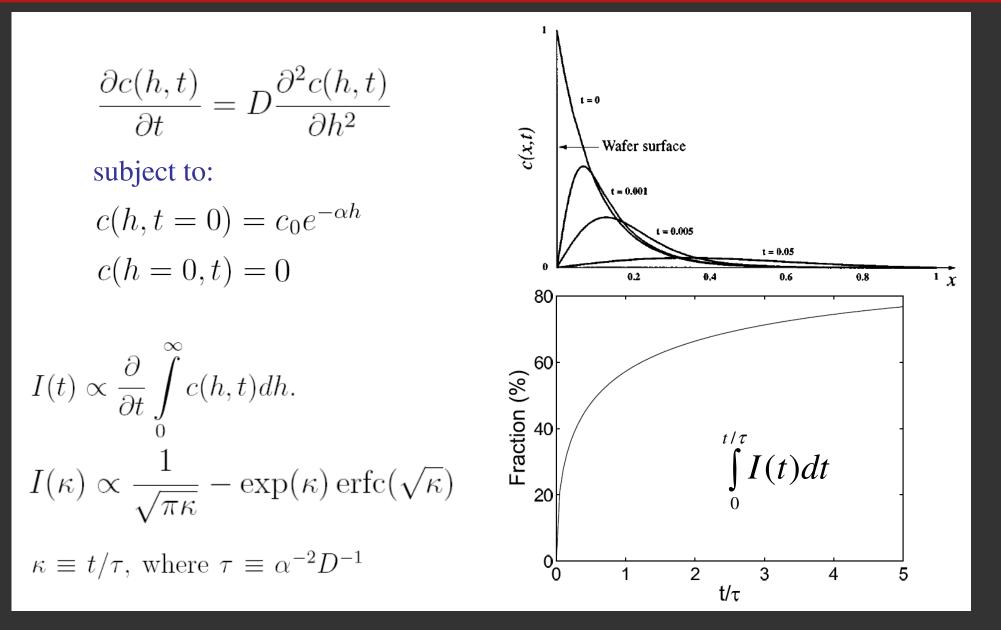


• Traditionally, it was believed that NEA cathodes are slow (~10s of ps); indeed, long emission tails were measured from GaAs for  $\lambda$  ~ 850nm





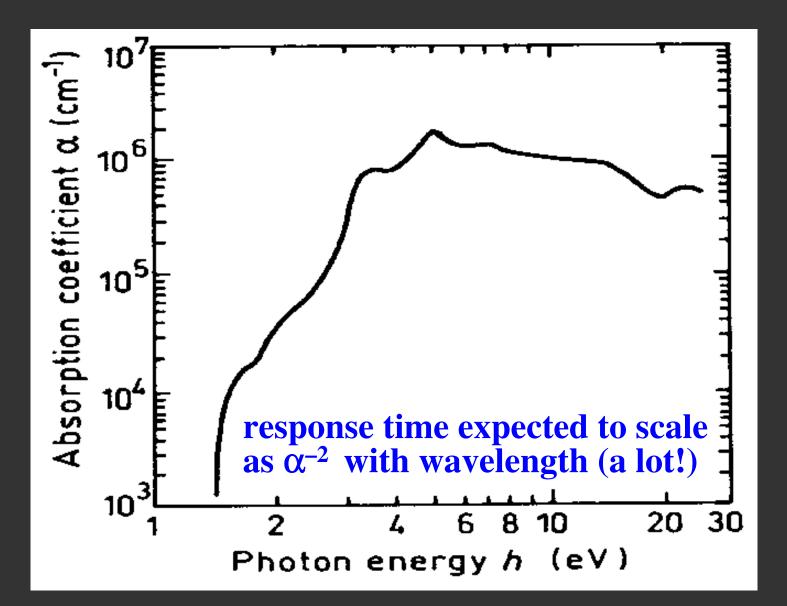
# **Diffusion model**



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### **GaAs** absorption

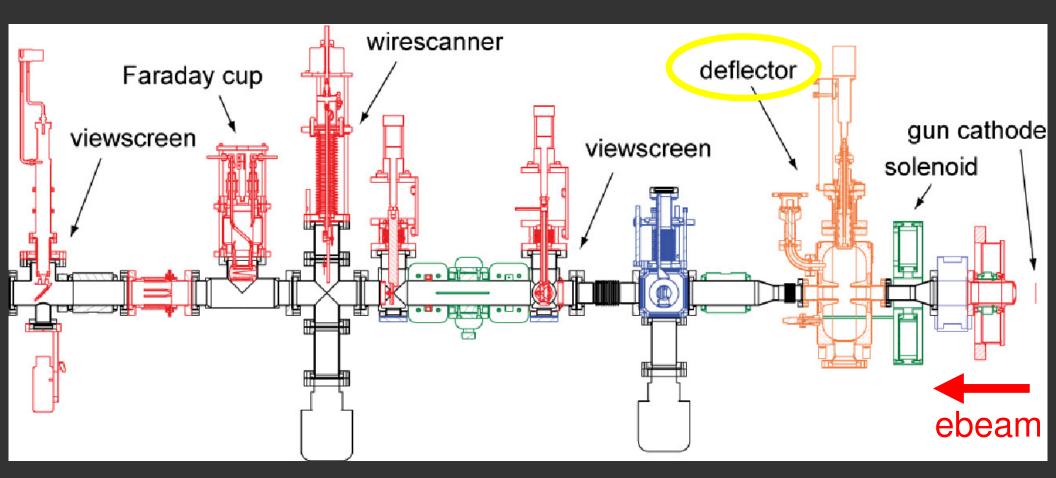




- Temporal response directly measured for GaAs and GaAsP for 520 nm (1 ps rms laser pulse)
- Measured indirectly using space charge effect for both photocathodes at 860, 785, 710, and 460 nm (~100 fs laser pulse)
- See Phys. Rev. ST-AB 11 (2008) 040702 for details



- RF synchronized to laser (1.2 ps rms jitter measured)
- Overall time resolution: 1.5 ps rms





 If solenoid is turned off, shorter response time ⇒ more space charge ⇒ larger spot size

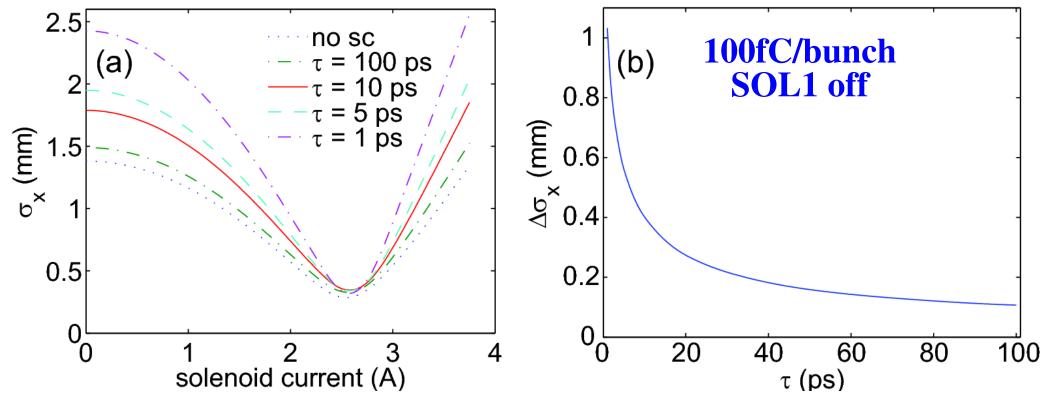
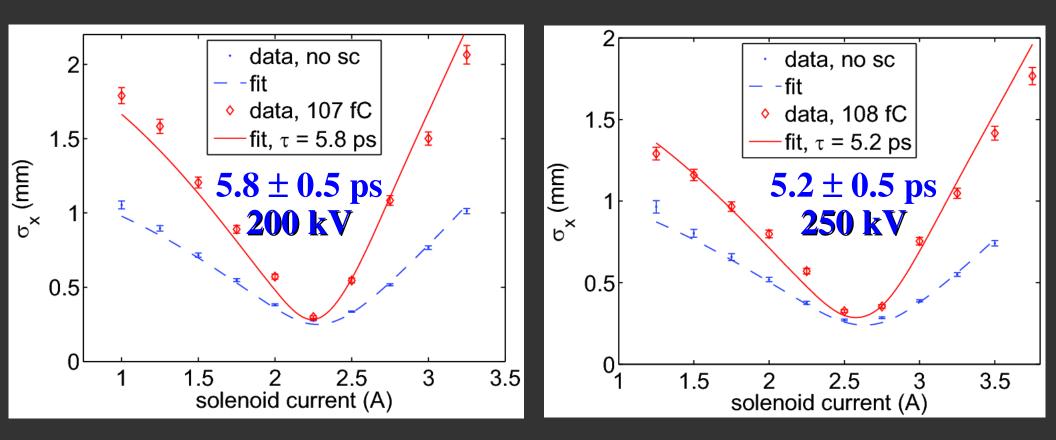


FIG. 11: Calculated dependence of the transverse beam size of the beam at the location of the wire scanner for different values of parameter  $\tau$ . Charge per bunch 100 fC, gun voltage 250 kV,  $k_BT_{\perp}$  150 meV, initial rms laser spot size 120  $\mu$ m. (a) Solenoid scan. (b) Change of the spot size relative to the case of negligible space charge for unpowered solenoid as a function of parameter  $\tau$ .

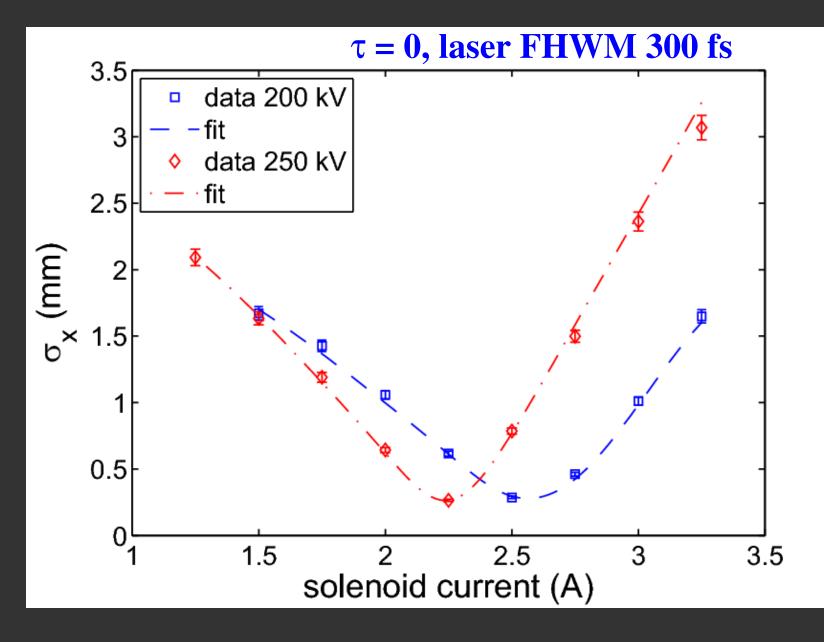


 Used Astra with preprogrammed temporal profile (diffusion model + convolution with laser profile) to fit observed data (only one variable parameter)





# Indirect method: 460 nm



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# Indirect method results

TABLE I: Results of data fitting for GaAs response time.		
Wavelength (nm)	$\tau \ (\mathrm{ps})$	Comment
860	$76{\pm}26$	$V_{gun} = 200 \text{ kV}$
860	$69{\pm}22$	$V_{gun} = 250 \text{ kV}$
785	$11.5 \pm 1.2$	$V_{gun} = 200 \text{ kV}$
785	$9.3 \pm 1.1$	$V_{gun} = 250 \text{ kV}$
710	$5.8 \pm 0.5$	$V_{gun} = 200 \text{ kV}$
710	$5.2 \pm 0.5$	$V_{gun} = 250 \text{ kV}$
520	$\leq 1$	upper estimate placed
460	$\leq 0.14$	upper estimate placed



**Direct meas.: GaAs** 

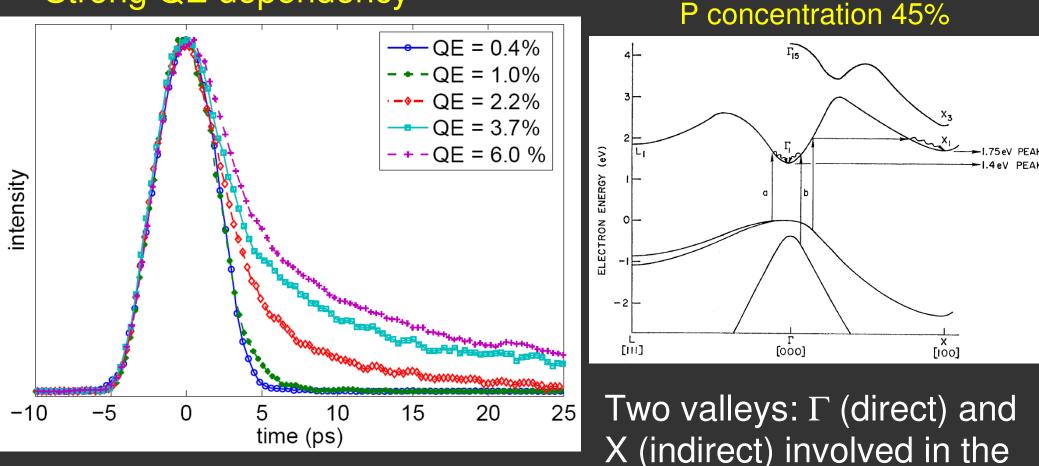
#### laser shaping response: 1ps rms laser QE = 10% QE = 5% intensity laser cross-correlation $N_{\rm AM}$ $N_{\rm AM}$ $N_{\rm AM}$ intensity -10 -20 10 20 0 time (ps) deflector off intensity ------10-5 0 5 10 time (ps) ebeam t-profile from deflector -20 -10 20 10 0 time (ps)

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# **Direct meas.: GaAsP**

#### Strong QE dependency



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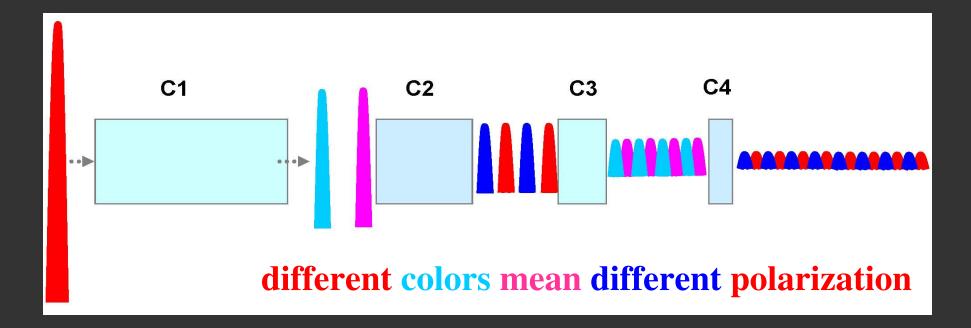
process



- GaAs is a prompt emitter (on ~1ps scale) at 520 nm
- GaAsP has longer tail (strong QE dependency) in addition to its larger thermal emittance
- This is thought to be due to emission from X CBM
- Also, have performed measurements on Cs:GaN photocathode at 260nm. Prompt emitter (on ~1ps scale). Thermal emittance data is work in process.



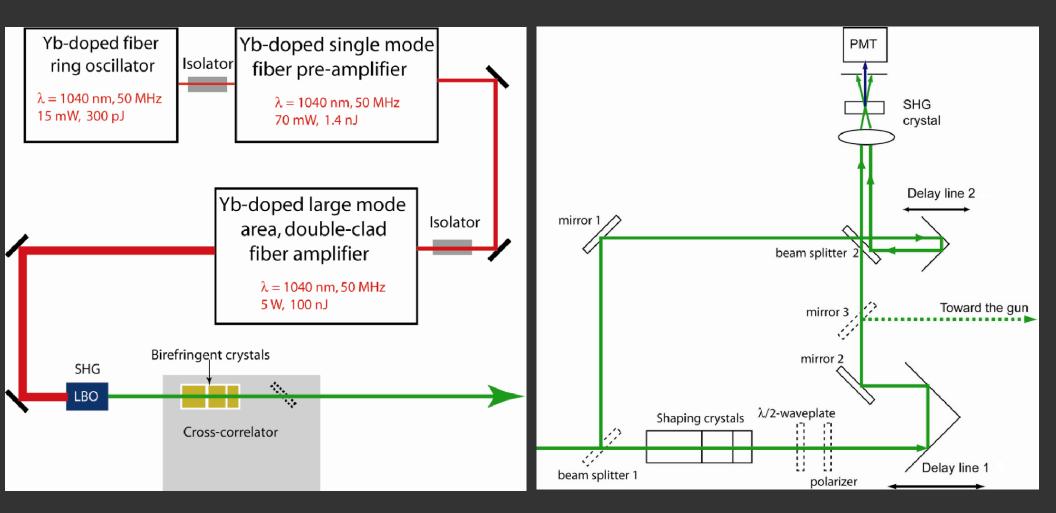
# **Temporal shaping**



 Use birefringent crystals to shape short laser pulse (very efficient)

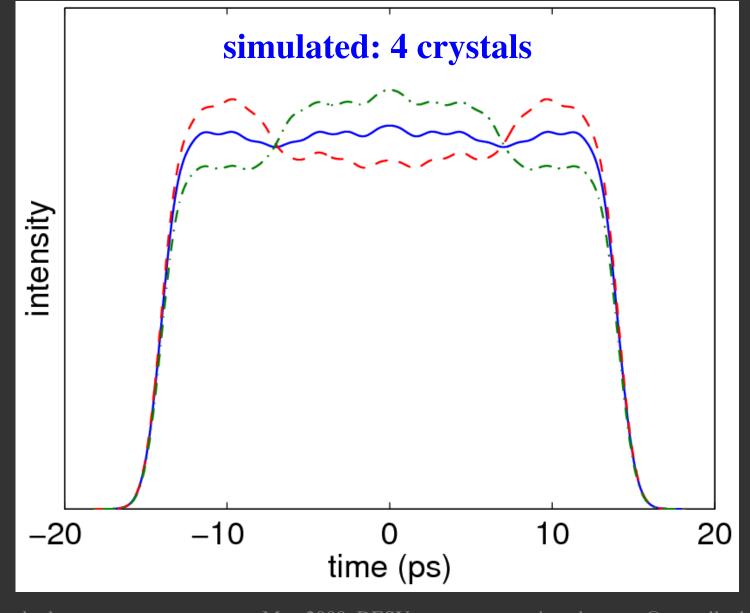


### Laser setup





### **Pulse stacking**

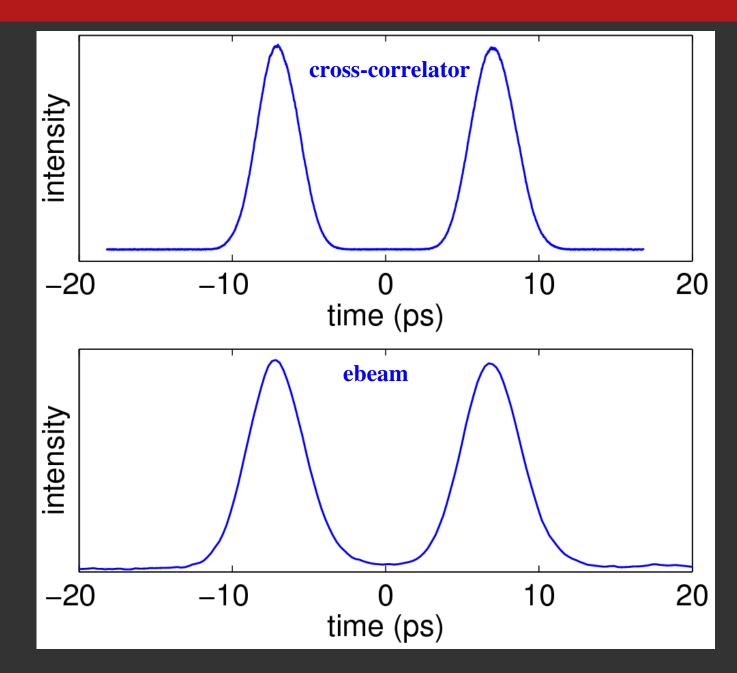


NEA photocathodes meas



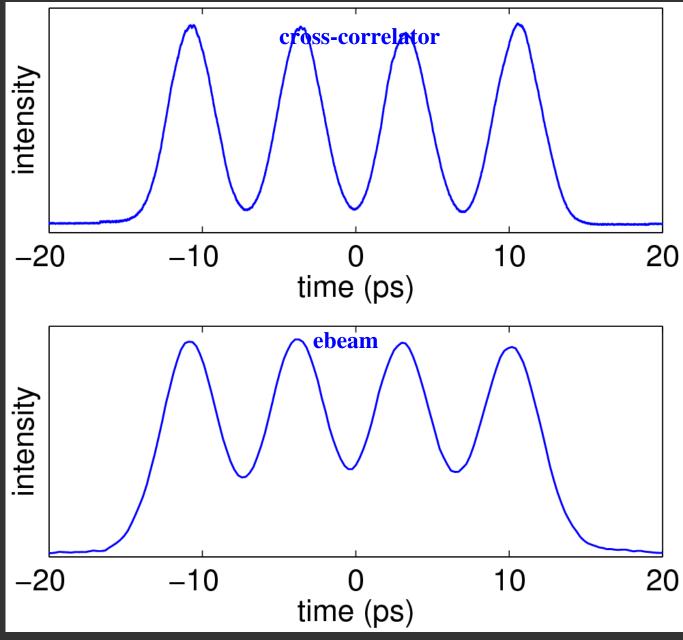


### Cornell University Ebeam vs. laser: 1 cryst





### Cornell University Ebeam vs. laser: 2 cryst



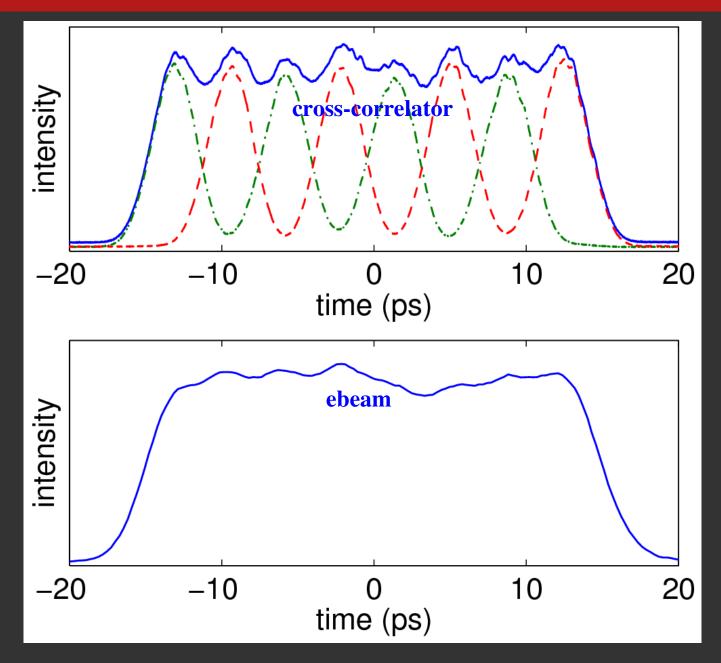
NEA photocathodes meas.

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# Ebeam vs. laser: 3 cryst



NEA photocathodes meas



- Essential properties of NEA photocathodes have been measured in wide range of laser wavelengths
- GaAs is the superior choice of what we have tried so far; at 520 nm the temporal response is ~ps or shorter; thermal emittance is 0.48 mm-mrad per 1mm rms laser spot (4mm diameter spot)



ERL team: John Barley, Sergey Belomestnykh, John Dobbins, Bruce Dunham, Fay Hannon, Yulin Li, Xianghong Liu, Bob Meller, Tsukasa Miyajima, Dimitre Ouzounov, Dave Rice, John Sikora, Charlie Sinclair, Karl Smolensky and more...

NSF for \$\$\$